

IN THE U.S. PATENT AND TRADEMARK OFFICE

20/552709

In re application of

Rikizo HATAKEYAMA et al.

Conf.

Application No. NEW NATIONAL PHASE

Group

Filed October 7, 2005

Examiner

METHOD AND APPARATUS FOR PRODUCING GAS ATOM CONTAINING FULLERENE,
AND GAS ATOM CONTAINING FULLERENE

**INFORMATION DISCLOSURE STATEMENT
(SUBMISSION CONCURRENT WITH THE
FILING OF A NEW PATENT APPLICATION)**

Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

October 7, 2005

Sir:

Pursuant to 37 C.F.R. §§ 1.97 and 1.98, and in fulfillment of the duty of disclosure under 37 C.F.R. § 1.56, applicant(s) hereby submit(s) an Information Disclosure Statement for consideration by the Examiner.

I. LIST OF PATENTS, PUBLICATIONS OR OTHER INFORMATION

The patents, publications, or other information submitted for consideration by the Office are listed on PTO-1449, attached hereto.

II. COPIES

- ☐ Copies of the U.S. patents or publications are not submitted since the USPTO has waived their submission for applications filed after June 30, 2003.
- ☒ Submitted herewith is a legible copy of (i) each foreign patent; (ii) each publication or that portion which caused it to be listed; and (iii) all other information or that portion which caused it to be listed.
- ☐ This application is a National Phase of a PCT application. Some or all of the documents listed on the PTO-1449 are not enclosed because they were cited in the International Search Report and copies should have been forwarded from the International Search Authority pursuant to the trilateral agreement between the USPTO, EPO and JPO, or they are U.S. patents or U.S. published applications. If copies are needed, please contact the undersigned.

III. CONCISE EXPLANATION OF THE RELEVANCE
(check at least one box)**10/552709**a. ☐ **DOCUMENTS IN THE ENGLISH LANGUAGE**

The attached non U.S. patents, non U.S. patent application publications, foreign publications, or other information in the English language do not require a statement of relevancy.

b. ☐ **DOCUMENTS NOT IN THE ENGLISH LANGUAGE**

A concise explanation of the relevance of all patents, publications, or other information listed that is not in the English language is as follows:

c. ☒ **FOREIGN SEARCH REPORT OR ACTION**

An English language version of the search report or action that indicates the degree of relevance found by the foreign office is attached, thereby satisfying the requirement for a concise explanation. See MPEP 609(A)(3).

d. ☐ **OTHER**

The following additional information is provided for the Examiner's consideration.

FEES

This Information Disclosure Statement is being filed concurrently with the filing of a new patent application; therefore, no fee is required.

If The Examiner has any questions concerning this IDS, he/she is requested to contact the undersigned.

Respectfully submitted,

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Enclosures: ☒ Form PTO-1449(s)
☒ Documents
☒ Foreign Search Report
☐ Other: _____

Receipt date: 10/07/2005

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Sheet 1 of 1

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)	Attorney Docket No.: 8075-1015	Application No.: NEW NATIONAL PHASE
	Applicant: Rikizo HATAKEYAMA et al.	
	Filing Date: October 7, 2005	Group Art Unit: 10/552709

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing date (if appropriate)

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
/HMC/	09-082495	3/28/1997	JAPAN English				
/HMC/	11-345772	12/14/1999	JAPAN abstracts				
/HMC/	2002-335004	11/22/2002	JAPAN considered				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

/HMC/	T. HIRATA et al., "The K+-C60 plasma for material processing", PLASMA SOURCES SCI. TECHNOL., 1996, Vol. 5, pages 288 to 292
/HMC/	R. HATAKEYAMA et al., "Formation of alkali- and Si-endohedralfullerenes based on plasma technology", ELECTROCHEMICAL SOCIETY PROCEEDINGS, 2001, Vol. 2001-11, pages 341 to 348
/HMC/	HATAKEYAMA R. et al., "Arch Hoden ni yoru Tanso Cluster no Gosei to Oyo, 6. Fullerene Plasma no Seishitsu to Oyo", Journal of Plasma and Fusion Research, 1999, Vol 75, No. 8, pages 927 to 933
/HMC/	HATAKEYAMA R., "Teijoteki Hoden Plasma no Gensho o Oyo", The Journal of the Japan Research Group of Electrical Discharges, 2002, Vol. 45, No. 4, pages 73 to 82
/HMC/	HOJJIN HUANG et al., "14 N@C 60 formation in a nitrogen rf-plasma, 2002, CHEM. COMMUN., NO. 18, pages 2076 to 2077
/HMC/	B. PIETZAK et al., "14@C60 CARBON, 1998, Vol. 36, Nos. 5 to 6, pages 613 to 615
/HMC/	S. WATANABE et al., "Synthesis of endohedral 133 Xe-fullerene by ion implantation", Japan Atomic Energy Research Institute, JAERI-Review, 2001, No. JAERI-Review, 2001-039, pages 228 to 229
	Koichi KOMATSU et al., "Naiho Fullerene no Yuki Gosei ni Idomu", Chemistry, 01 February, 2004 (01.02.04), Vol. 59, No.2, pages 23 to 28

EXAMINER: /Heng M. Chan/

DATE CONSIDERED 02/18/2009

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

* English language abstract provided for the Examiner's convenience

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ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /HMC/